

PATENT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Michael Weber-Grabau, et al.

Application No.: 09/927,102

Filed: August 10, 2001

For: CRITICAL DIMENSION  
METROLOGY SYSTEM  
INTEGRATED INTO  
SEMICONDUCTOR WAFER  
PROCESS TOOL

Group Art Unit: 2877

Examiner: Richard A. Rosenberger

**RESPONSE TO OFFICE ACTION  
MAILED OCTOBER 3, 2003**

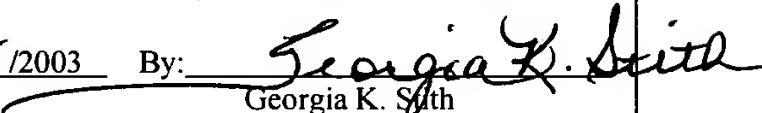
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Alexandria, VA 22313-1450

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on Dec. 15, 2003.

STALLMAN & POLLOCK LLP

Dated: 12/15/2003 By: 

Georgia K. Smith

Sir:

In response to the Office Action mailed October 3, 2003, please amend the above-identified application as follows:

**Amendment to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 10 of this paper.

12/18/2003 CNGUYEN 00000029 09927102

01 FC:2202                    18.00 OP  
02 FC:2201                    86.00 OP

Atty Docket No.: TWI-31000